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Patent Application No. 10/802,564
Customer Number: 42717

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Chun-Chieh Lin, et al.	§	Docket No.:	24061.465
		§		(TSMC2002-0110)
Serial No.:	10/802,564	§		
		§	Examiner:	Hoai V. Pham
Filing Date:	March 17, 2004	§		
		§	Art Unit:	2814
For:	Method of a Non-Metal Barrier	§		
	Copper Damascene Integration	§	Conf. No.:	3511

RESPONSE TO RESTRICTION REQUIREMENT

Mail Stop: Amendment
Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Dear Sir:

In response to the Office Action mailed July 16, 2004, applicant hereby elects, Group II, Claims 1-20, which are drawn to a method of making a semiconductor device.

Applicant's election is made with traverse on the grounds that the embodiments delineated by the examiner are not patentably distinct and therefore constitute a single invention concept.

An early action on the merits is respectfully requested.

Respectfully submitted,

T. F. Bliss

Timothy F. Bliss
Registration No. 50,925

Date: 8/16/04

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CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service as first class mail in an envelope addressed to: Mail Stop: Amendment, Commissioner For Patents, PO Box 1450, Alexandria, VA 22313-1450 on the date below.

Name

Date

Gayle Conner
8-16-04